Appl. No. 10/705,374 Amdt. dated February 13, 2007 Reply to Office action of 08/14/2006

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Amendments to the Abstract:

Please replace the paragraph beginning at page 7, line 3, with the following rewritten paragraph:

A cleaning mechanism for system having a combination of a substrate and a frame layer being cleaned includes an image sensor package, the cleaning mechanism a sealed up body is formed with a cleaning room. A rotating device is located within the cleaning room of the sealed up body. A cleaning device is mounted on the a side of the cleaning room of the sealed up body, and ejects a cleaner directly into the chamber in a direction opposite to a direction of a centrifugal force of the combination of the substrate and the frame layer, is cleaned a chamber of a substrate by cleaner. The rotating device is configured to fix the combination of the substrate and the chamber facing the cleaning device.